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C07C 39/16(21)Application number : **06-178638**(71)Applicant : **MITSUBISHI CHEM CORP**(22)Date of filing : **29.07.1994**(72)Inventor : **SUGAWARA TAKAHIRO**
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SUZUKI TOSHITAKA**(54) ION EXCHANGE RESIN**

(57)Abstract:

PURPOSE: To produce bisphenol-A by condensation reaction of acetone and phenols which gives a high conversion rate of acetone and is economically advantageous by producing ionic bonds of N,N,N-triethyl-3-mercaptopropyl ammonium.

CONSTITUTION: This strong acid sulfonic acid-type ion exchange resin is prepared by producing ionic bonds of N,N,N-triethyl-3-mercaptopropyl ammonium. To bond N,N,N-triethyl-3-mercaptopropyl ammonium to the sulfonic acid groups of the strong acid ion exchange resin, for example, the counter anion of N,N,N-triethyl-3-mercaptopropyl ammonium dissolved in ion-exchanged water is preliminarily converted into anions which can easily exchange ions with sulfonic acid anion such as acetate anion, carbonate anion, then the soln. is added to the strong acid ion exchange resin dispersed in ion-exchanged water and stirred for 0.1 to 2 hours.

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